

**Group Art Unit**  
**2881**

* EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE
21	AA	4,200,395	04/29/1980	Smith et al.	356	356	05/03/1977
	AB	4,332,473	06/01/1982	Ono	356	356	01/22/1980
	AC	5,867,276	02/02/1999	McNeil et al.	356	445	03/07/1997
	AD	5,963,329	10/05/1999	Conrad et al.	356	372	10/31/1997
30	AE	6,100,985	08/08/2000	Scheiner et al.	356	381	03/12/1999

	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
3	AF	0 281 030	02/26/1988	EPO	G03B	41/00		
	AG	WO 99/45340	09/10/1999	PCT	G01B	11/02		
3	AH	EP 0 965 889 A2	12/22/1999	EPO	G03F	9/00		

30	AI	T.K. Gaylord et al., "Analysis and Applications of Optical Diffraction by Gratings," <i>PROC. IEEE</i> , Vol. 73, No. 5, 1985, pp. 894-937.
1	AJ	M.G. Moharam et al., "Stable implementation of the rigorous coupled-wave analysis for surface-relief gratings: enhanced transmittance matrix approach," <i>J. Opt. Soc. Am. A</i> , Vol. 12, No. 5, May 1995, pp. 1077-1086.
	AK	M.G. Moharam et al., "Rigorous coupled-wave analysis of planar-grating diffraction," <i>J. Opt. Soc. Am.</i> , Vol. 71, No. 7, July 1981, pp. 811-818.
	AL	C.J. Raymond et al., "Scatterometry for CD measurements of etched structures," <i>Proceedings of the SPIE, SPIE, Bellingham, VA (U.S.A.)</i> , Vol. 2725, 1996, pp. 720-728.
	AM	M.R. Murnane et al., "Developed photoresist metrology using scatterometry," <i>Proceedings of the SPIE, SPIE, Bellingham, VA (U.S.A.)</i> , Vol. 2196, 1994, pp. 47-59.
30	AN	C.J. Raymond et al., "Metrology of subwavelength photoresist gratings using optical scatterometry," <i>Journal of Vacuum Science &amp; Technology B</i> , Vol. 13, No. 4, 1 July 1995, pp. 1484-1495.

Examiner <i>Z. Alan Loh</i>	Date Considered <i>5/11/04</i>
Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	